

WHAT IS CLAIMED IS:

Sub 917. 1. A semiconductor manufacturing apparatus for a photolithographic process including a coating process and a developing process, the apparatus comprising:

5 a first port where a substrate comes in and goes out;

 a second port, having a constant distance from the first port, where the substrate comes in and goes out;

 coating means, coupling the first port to the second port, for carrying the substrate between the first port and the second port and performing the coating process; and

10 11 developing means, coupling the first port to the second port, for carrying the substrate between the first port and the second port and performing the developing process, the developing means being stacked on the coating means in line.

15 2. The apparatus of Claim 1, wherein the coating means includes:

 a first path which couples the first port to the second port;

 a coating module which is arranged along one side of the first path; and

 a first carrier, which moves between the first port and the second port, for carrying a substrate to the first port or the second port or the coating module,

 wherein the developing means includes:

20 a second path which couples the first port to the second port;

 a developing module which is arranged along one side of the second path; and

 a second carrier, which moves between the first port and the second port, for carrying the substrate to the first port or the second port or the developing module.

25 3. The apparatus of Claim 1, wherein the second port is coupled to an exposure system.

30 4. The apparatus of Claim 1, wherein the coating means and the developing means are isolated from each other by an intermediate wall.

Sub 922. 5. The apparatus of Claim 2, wherein the coating module includes:

 a coater which is arranged at one side of the first path; and

 a bake unit which is arranged at the other side of the first path and opposite to the coater, and

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wherein the developing module includes:
a developer which is arranged at one side of the second path; and
a bake unit which is arranged at the other side of the second path and opposite to the developer.

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6. The apparatus of Claim 4 further comprising an air-conditioning apparatus, which is installed at the intermediate wall, for removing particles created in the coating means and the developing means.

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7. The apparatus of Claim 5, wherein the bake unit includes:
at least one heating plate for heating up a substrate; and
at least one cooling plate for cooling down the heated substrate.

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